

PHOTOSENSITIVE SEMICONDUCTOR NANOCRYSTALS,  
PHOTOSENSITIVE COMPOSITION COMPRISING SEMICONDUCTOR  
NANOCRYSTALS AND METHOD FOR FORMING SEMICONDUCTOR NANOCRYSTAL  
PATTERN USING THE SAME

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BACKGROUND OF THE INVENTION

This non-provisional application claims priority under  
35 U.S.C. § 119(a) to Korean Patent Application No. 2003-73338  
filed on October 21, 2003, which is herein incorporated by  
reference.

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Field of the Invention

The present invention relates to photosensitive  
semiconductor nanocrystals, a photosensitive composition  
comprising semiconductor nanocrystals and a method for forming  
a semiconductor nanocrystal pattern using the same. More  
particularly, the present invention relates to semiconductor  
nanocrystals that are surface-coordinated with a compound  
containing a photosensitive functional group, a photosensitive  
composition comprising semiconductor nanocrystals, and a  
method for forming a semiconductor nanocrystal pattern by  
forming a film using the photosensitive semiconductor  
nanocrystals or the photosensitive composition, exposing the  
film to light and developing the exposed film.

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### Description of the Related Art

Due to the quantum confinement effects of compound semiconductor nanocrystals (i.e. quantum dots), the characteristic energy bandgap of semiconductor materials are changed. Since the control over the materials, structure, shape and size of the nanocrystals enables the control of the corresponding bandgaps, various energy levels can be obtained.

In recent years, there have been many trials to prepare semiconductor nanocrystals by a wet chemistry method wherein a precursor material is added to an organic solvent and nanocrystals are grown so as to have an intended size.

According to the wet chemistry method, as the nanocrystals are grown, the organic solvent is naturally coordinated to the surface of the nanocrystals and acts as a dispersant.

Accordingly, the organic solvent allows the nanocrystals to grow in the nanometer-scale level. Using vapor deposition processes, e.g., MOCVD (metal organic chemical deposition) and MBE (molecular beam epitaxy), it is difficult to uniformly control the size, shape and density of nanocrystals. In contrast, the wet chemistry method has an advantage in that nanocrystals can be uniformly synthesized in various sizes by appropriately controlling the concentration of precursors used, the kind of organic solvents, synthesizing temperature and time, etc.

However, since nanocrystals prepared by the wet

chemistry method are commonly dispersed in an organic solvent, such as toluene or chloroform, techniques of forming a thin film as well as pattern forming method of nanocrystals are required in order to apply the nanocrystals to electronic devices. Patterning techniques reported hitherto are mainly associated with the patterning of nanocrystals by vapor deposition. These techniques, however, have a shortcoming in that control over the uniformity of size, shape, and density is difficult (Appl. Phys. Letter, 1997, 70, 3140).

In this regard, U.S. Patent No. 5,559,057 suggests a method for forming a pattern of nanocrystals which comprises the steps of vapor-depositing or spraying nanocrystals using a mask to deposit nanocrystals only on the areas not covered with a mask, irradiating the nanocrystals with an electron beam to produce a thin film, and removing the mask. U.S. Patent No. 6,139,626 discloses a method for indirectly forming a pattern of nanocrystals by filling in pores of a template with nanocrystals wherein the template may be patterned in any configuration. However, these patterning methods involve the use of a high-energy electron beam and a troublesome lift-off operation of the mask used. In addition, the template material may affect the performances of the pattern to be formed, and there is thus a limitation in the kind of materials that can be patterned.

Further, U.S. Patent. No. 5,751,018 discloses a method

for aligning nanocrystals using terminal groups of a self-assembled monolayer formed on a metal substrate. U.S. Patent No. 6,602,671 describes a method for binding dispersed nanocrystals to a polymeric support. Since the above-mentioned methods are not substantially associated with patterning, they have limited applicability to the patterning of nanocrystals.

Thus, there exists a need in the art for a method for forming a pattern of semiconductor nanocrystals in a simple manner, without the use of a template or a deposition process requiring high vacuum and high temperature conditions.

#### SUMMARY OF THE INVENTION

A feature of the present invention is to provide novel photosensitive semiconductor nanocrystals for forming a semiconductor nanocrystal pattern.

Another feature of the present invention is to provide a novel photosensitive composition comprising semiconductor nanocrystals for forming a semiconductor nanocrystal pattern.

Still another feature of the present invention is to provide a method for forming a semiconductor nanocrystal pattern using the above photosensitive semiconductor nanocrystals and the photosensitive composition.

In accordance with a feature of the present invention, there is provided semiconductor nanocrystals surface-

coordinated with a compound containing a photosensitive functional group.

In accordance with another feature of the present invention, there is provided a photosensitive composition for a semiconductor nanocrystal pattern, comprising i) semiconductor nanocrystals, and ii) a photocurable compound.

In accordance with still another feature of the present invention, there is provided a method for forming a semiconductor nanocrystal pattern, comprising the steps of: i) producing a semiconductor nanocrystal film using the above semiconductor nanocrystals or the above photosensitive composition; ii) exposing the film through a mask; and iii) developing the exposed film.

In accordance with still another feature of the present invention, there is provided an organic-inorganic hybrid electroluminescent device, wherein the semiconductor nanocrystal pattern prepared according to the above method is contained as a luminescent layer.

#### BRIEF DESCRIPTION OF THE DRAWINGS

The above and other objects, features and other advantages of the present invention will be more clearly understood from the following detailed description taken in conjunction with the accompanying drawings, in which:

Fig. 1 is a schematic diagram of a semiconductor

nanocrystal surface-coordinated with a compound containing a photosensitive functional group;

Fig. 2 is a photograph of a semiconductor nanocrystal pattern prepared in Example 1 of the present invention  
5 (enlarged by 1000 times, taken with UV microscope);

Fig. 3 is a photograph of a semiconductor nanocrystal pattern prepared in Example 3 of the present invention  
(enlarged by 1000 times, taken with UV microscope);

Fig. 4 is a photograph of a semiconductor nanocrystal  
10 pattern prepared in Example 4 of the present invention  
(enlarged by 1000 times, taken with UV microscope);

Figs. 5a and 5b are an optical microscopic image (x 1,000) and an AFM image of the semiconductor nanocrystal pattern of Fig. 4; and

15 Fig. 6 is an electroluminescent spectrum of a  
electroluminescent device manufactured in Example 8 of the  
present invention.

#### DETAILED DESCRIPTION OF THE PRESENT INVENTION

20 Hereinafter, the present invention will be explained in  
more detail with reference to the accompanying drawings.

#### Photosensitive semiconductor nanocrystals

The photosensitive semiconductor nanocrystals of the  
25 present invention are semiconductor nanocrystals surface-

coordinated with a compound containing a photosensitive functional group.

Semiconductor nanocrystals usable in the present invention may include all semiconductor nanocrystals prepared from metal precursors by a wet chemistry method. For example, the semiconductor nanocrystals may be prepared by adding a corresponding metal precursor to an organic solvent in the absence or presence of a dispersant, and growing crystals at a predetermined temperature. Examples of suitable semiconductor nanocrystals usable in the present invention include Group II-IV, III-IV and V compound nanocrystals and mixtures thereof. More preferred examples of nanocrystals include, but are not limited to, CdS, CdSe, CdTe, ZnS, ZnSe, ZnTe, HgS, HgSe, HgTe, GaN, GaP, GaAs, InP, InAs and mixtures thereof. If the semiconductor nanocrystals are composed of two or more compounds, it may be a uniformly mixed type, gradiently mixed type, core-shell type or ally type.

The photosensitive compound coordinated to the surface of the semiconductor nanocrystals is a compound wherein a photoreactive functional group (e.g., carbon-carbon double bond or acryl group) is selectively bonded to a linker (e.g., cyanide, thiol (SH), amino, carboxylic acid group or phosphonic acid group). Selectively, there may be an alkylene, amide, phenylene, biphenylene, ester or ether group between the photoreactive functional group and the linker.

Preferably, the photosensitive compound is represented by  
Formula 1 below:



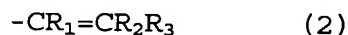
5            wherein X is NC-, HOOC-, HRN-, POOOH-, RS- or RSS- (in  
which R is a hydrogen atom or a C<sub>1-10</sub> saturated or unsaturated  
aliphatic hydrocarbon group); A is a direct bond, an aliphatic  
organic group, a phenylene group or a biphenylene group; and B  
is an organic group containing at least one carbon-carbon  
10 double bond, which may be substituted with at least one group  
selected from the group consisting of -CN, -COOH, halogen  
groups, C<sub>1-5</sub> halogenated alkyl groups, amine groups, C<sub>6-15</sub>  
aromatic hydrocarbon groups, and C<sub>6-12</sub> aromatic hydrocarbon  
groups substituted with F, Cl, Br, a halogenated alkyl group,  
15 R'O- (in which R' is a hydrogen atom or a C<sub>1-5</sub> alkyl group), -  
COOH, an amine group or -NO<sub>2</sub>.

More preferably, the aliphatic organic group in the  
substituent A of Formula 1 is a saturated aliphatic  
hydrocarbon group such as -(CR<sub>2</sub>)<sub>n</sub>- (in which R is a hydrogen  
20 atom, a C<sub>1-5</sub> alkyl group, and n is an integer of 1~30), an  
aliphatic ester group containing an ester moiety (-COO-), an  
aliphatic amide group containing an amide moiety (-NHCO-), an  
aliphatic oxycarbonyl group containing an oxycarbonyl moiety  
(-OCO-), or an aliphatic ether group containing an ether  
25 moiety (-O-). The aliphatic organic group may be branched



with a C<sub>1-5</sub> alkyl group, or may be substituted with by a hydroxyl, amine or thiol group.

More preferably, the moiety B in Formula 1 is an organic group represented by Formula 2 below:



wherein R<sub>1</sub> is a hydrogen atom, -COOH, a halogen group, a C<sub>1-5</sub> alkyl group or a halogenated alkyl group; and R<sub>2</sub> and R<sub>3</sub> are each independently a hydrogen atom, a C<sub>1-30</sub> alkyl group, -CN, -COOH, a halogen group, a C<sub>1-5</sub> halogenated alkyl group, a C<sub>2-30</sub> unsaturated aliphatic hydrocarbon group containing at least one carbon-carbon double bond, a C<sub>6-12</sub> aromatic hydrocarbon group substituted or unsubstituted with F, Cl, Br, hydroxyl, a C<sub>1-5</sub> halogenated alkyl group, an amine group, R'O- (in which R' is a C<sub>1-5</sub> alkyl group), -COOH or -NO<sub>2</sub>.

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15  
In the moieties R<sub>2</sub> and R<sub>3</sub> of Formula 2, the C<sub>1-30</sub> alkyl group and the C<sub>2-30</sub> unsaturated aliphatic hydrocarbon group containing at least one carbon-carbon double bond may be branched by an alkyl group, and if necessary, may be substituted with a hydroxyl group, a carboxyl group, etc. The number of the double bonds in the unsaturated aliphatic hydrocarbon group is not especially limited, but is preferably 3 or less.

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Preferred examples of the compound represented by Formula 1 include, but are not limited to, methacrylic acid,

crotonic acid, vinylacetic acid, tiglic acid, 3,3-  
 dimethylacrylic acid, trans-2-pentenoic acid, 4-pentenoic  
 acid, trans-2-methyl-2-pentenoic acid, 2,2-dimethyl-4-  
 pentenoic acid, trans-2-hexenoic acid, trans-3-hexenoic acid,  
 5 2-ethyl-2-hexenoic acid, 6-heptenoic acid, 2-octenoic acid,  
 citronellic acid, undecylenic acid, myristoleic acid,  
 palmitoleic acid, oleic acid, elaidic acid, cis-11-elcosenoic  
 acid, euric acid, nervonic acid, trans-2,4-pentadienoic acid,  
 2,4-hexadienoic acid, 2,6-heptadienoic acid, geranic acid,  
 10 linoleic acid, 11,14-eicosadienoic acid, cis-8,11,14-  
 eicosatrienoic acid, arachidonic acid, cis-5,8,11,14,17-  
 eicosapentaenoic acid, cis-4,7,10,13,16,19-docosahexaenoic  
 acid, fumaric acid, maleic acid, itaconic acid, ciraconic  
 acid, mesaconic acid, trans-glutaconic acid, trans-beta-  
 15 hydromuconic acid, trans-traumatic acid, trans-muconic acid,  
 cis-aconitic acid, trans-aconitic acid, cis-3-chloroacrylic  
 acid, trans-3-chloroacrylic acid, 2-bromoacrylic acid, 2-  
 (trifluoromethyl)acrylic acid, trans-styrylacetic acid, trans-  
 cinnamic acid,  $\alpha$ -methylcinnamic acid, 2-methylcinnamic acid,  
 20 2-fluorocinnamic acid, 2-(trifluoromethyl)cinnamic acid, 2-  
 chlorocinnamic acid, 2-methoxycinnamic acid, 2-hydroxycinnamic  
 acid, 2-nitrocinnamic acid, 2-carboxycinnamic acid, trans-3-  
 fluorocinnamic acid, 3-(trifluoromethyl)cinnamic acid, 3-  
 chlorocinnamic acid, 3-bromocinnamic acid, 3-methoxycinnamic  
 25 acid, 3-hydroxycinnamic acid, 3-nitrocinnamic acid, 4-

methyleinnamic acid, 4-fluorocinnamic acid, trans-4-  
(trifluoromethyl)-cinnamic acid, 4-chlorocinnamic acid, 4-  
bromocinnamic acid, 4-methoxycinnamic acid, 4-hydroxycinnamic  
acid, 4-nitrocinnamic acid, 3,3-dimethoxycinnamic acid, 4-  
5 vinylbenzoic acid, allyl methyl sulfide, allyl disulfide,  
diallyl amine, oleylamine, 3-amino-1-propanol vinyl ether, 4-  
chlorocinnamionitrile, 4-methoxycinnamionitrile, 3,4-  
dimethoxycinnamionitrile, 4-dimethylaminocinnamionitrile,  
acrylonitrile, allyl cyanide, crotonionitrile,  
10 methacrylonitrile, cis-2-pentenionitrile, trans-3-  
pentenionitrile, 3,7-dimethyl-2,6-octadienionitrile and 1,4-  
dicyano-2-butene.

The photosensitive semiconductor nanocrystals of the  
present invention can be prepared by obtaining nanocrystals  
15 from a corresponding metal precursor, dispersing the obtained  
nanocrystals in an organic solvent, and treating the  
dispersion with the photosensitive compound of Formula 1. The  
treatment with the photosensitive compound is not especially  
limited, but is preferably carried out by refluxing the  
20 dispersion of the nanocrystals in the presence of the  
photosensitive compound. The reflux conditions, including  
time and temperature, and the concentration of the  
photosensitive compound can be properly controlled according  
to the kind of the dispersing solvent, the nanocrystals and  
25 the photosensitive compound coordinated to the surface of the

nanocrystals. Alternatively, nanocrystals are surface-coordinated with a dispersant having a reactive end group, such as mercaptopropanol, and then reacted with a photosensitive compound capable of reacting with the reactive end group of the dispersant, such as methacryloyl chloride, thereby producing nanocrystals surface-coordinated with the photosensitive compound.

Still alternatively, semiconductor nanocrystals may be directly surface-coordinated with a photosensitive compound by adding a metal precursor into an organic solvent and growing crystals at the predetermined temperature in the presence of the photosensitive compound. The kind of organic solvent, the crystal-growth temperature and the concentration of the precursor can be appropriately varied according to the kind of the photosensitive compound, and the kind, size and shape of the desired semiconductor nanocrystals.

A preferred embodiment of the photosensitive semiconductor nanocrystals according to the present invention is schematically shown in Fig. 1. As shown in Fig. 1, X is a linker binding the semiconductor nanocrystals to a photosensitive functional group such as aryl or vinyl group. The surface-coordinating rate of the photosensitive compound to the semiconductor nanocrystals can be appropriately controlled by changing the mixing ratio of the nanocrystals and the compound.

Photosensitive composition for pattern formation of  
semiconductor nanocrystals

The photosensitive composition of the present invention  
5 comprises i) semiconductor nanocrystals, and ii) a  
photocurable compound

As to the semiconductor nanocrystals, common  
semiconductor nanocrystals or photosensitive semiconductor  
nanocrystals according to the present invention may be used.  
10 Where photosensitive semiconductor nanocrystals of the present  
invention are used, it is advantageous that substitution with  
a compound containing a photosensitive functional group is  
unnecessary. The semiconductor nanocrystals contained in the  
photosensitive composition of the present invention are as  
15 described above.

As to the photocurable compound contained in the  
photosensitive composition, polymers containing at least one  
acryl and/or vinyl group and ether-based compounds can be  
used. More concretely, polymers containing at least one acryl  
20 and/or vinyl group include multifunctional acrylate-based  
compounds, multifunctional polyalkyleneoxide compounds and  
polysiloxanes containing at least one acryl and/or vinyl  
group.

Preferred examples of the photocurable compound include,  
25 but are not limited to, allyloxylated cyclohexyl diacrylate,

bis(acryloxy ethyl)hydroxyl isocyanurate, bis(acryloxy  
 neopentylglycol) adipate, bisphenol A diacrylate, bisphenyl A  
 dimethacrylate, 1,4-butanediol diacrylate, 1,4-butanediol  
 dimethacrylate, 1,3-butyleneglycol diacrylate, 1,3-  
 5 butyleneglycol dimethacrylate, dicyclopentanyl diacrylate,  
 diethyleneglycol diacrylate, diethyleneglycol dimethacrylate,  
 dipentaerythriol hexaacrylate, dipentaerythriol monohydroxy  
 pentacrylate, ditrimethylolprpane tetraacrylate,  
 ethyleneglycol dimethacrylate, glycerol methacrylate, 1,6-  
 10 hexanediol diacrylate, neopentylglycol dimethacrylate,  
 neopentylglycol hydroxypivalate diacrylate, pentaerythritol  
 triacrylate, pentaerythritol tetraacrylate, phosphoric acid  
 dimethacrylate, polyetyleneglycol diacrylate,  
 polypropyleneglycol diacrylate, tetraethyleneglycol  
 15 diacrylate, tetrabromobisphenol A diacrylate,  
 triethyleneglycol divinylether, triglycerol diacrylate,  
 trimethylolpropane triacrylate, tripropyleneglycol diacrylate,  
 tris(acryloxyethyl)isocyanurate, phosphoric acid triacrylate,  
 phosphoric acid diacrylate, acrylic acid propargyl ester,  
 20 vinyl terminated polydimethylsiloxane, vinyl terminated  
 diphenylsiloxane-dimethylsiloxane copolymer, vinyl terminated  
 polyphenylmethyilsiloxane, vinyl terminated  
 trifluoromethylsiloxane-dimethylsiloxane copolymer, vinyl  
 terminated diethylsiloxane-dimethylsiloxane copolymer,  
 25 vinylmethyilsiloxane, monomethacryloyloxypropyl terminated

polydimethyl siloxane, monovinyl terminated polydimethyl siloxane and monoallyl-mono trimethylsiloxyl terminated polyethylene oxide.

The composition ratio of i) the semiconductor nanocrystals and ii) the photocurable compound contained in the photosensitive composition of the present invention is not especially limited, and can be properly controlled depending on the photocurability (i.e. curing rate, state of a cured film, etc.), binding ability between the photosensitive compound and the nanocrystals, etc.

#### Pattern formation of semiconductor nanocrystals

A semiconductor nanocrystal pattern can be formed by a) forming a semiconductor nanocrystal film using the photosensitive semiconductor nanocrystals or the photosensitive composition according to the present invention; b) exposing the film through mask; and c) developing the exposed film.

In step a), the semiconductor nanocrystal film is produced by dispersing the photosensitive semiconductor nanocrystals or the photosensitive composition according to the present invention in a suitable organic solvent, and coating the dispersion onto a substrate. At this step, a photoinitiator may be added to the organic solvent. Unlike common photolithographic techniques, the photosensitive

semiconductor nanocrystals or the photosensitive composition according to the present invention may be cured without a photoinitiator. However, if necessary, a photoinitiator may be used to assist the crosslinking reaction. Examples of photoinitiators usable in the present invention include those capable of forming free radicals upon light irradiation, such as acetophenone-, benzoin-, benzophenone- and thioxantone-based photoinitiators. Examples of the acetophenone-based initiator usable in the present invention include 4-phenoxy dichloroacetophenone, 4-t-butyl dichloroacetophenone, 4-t-butyl trichloroacetophenone, diethoxyacetophenone, 2-hydroxy-2-methyl-1-phenyl-propane-1-one, 1-(4-isopropylphenyl)-2-hydroxy-2-methylpropane-1-one, 1-(4-dodecylphenyl)-2-hydroxy-2-methylpropane-1-one, 4-(2-hydroxyethoxy)-phenyl-(2-hydroxy-2-propyl)ketone, 1-hydroxy cyclohexyl phenyl ketone, 2-methyl-1-[4-(methylthio)phenyl]-2-morpholino-propane-1, and the like. Examples of the benzoin-based photoinitiator include benzoin, benzoin methyl ether, benzoin ethyl ether, benzoin isopropyl ether, benzoin isobutyl ether, benzyl dimethyl ketal, etc. Examples of the benzophenone-based photoinitiator include benzophenone, benzoyl benzoic acid, benzoyl benzoic acid methyl ester, 4-phenyl benzophenone, hydroxy benzophenone, 4-benzoyl-4'-methyl diphenyl sulphide, 3,3'-dimethyl-4-methoxy benzophenone and the like.

An organic solvent used in this process is not



especially limited, but preferably those capable of homogeneously dispersing nanocrystals and being easily removed after application are used. More preferably, DMF, 4-hydroxy-4-methyl-2-pentanone, ethylene glycol monoethyl ether, 2-methoxyethanol, chloroform, chlorobenzene, toluene, tetrahydrofuran, dichloromethane, hexane, heptane, octane, nonane, decane or a mixture thereof is used. The application may be carried out by a spin coating, dip coating, spray coating or blade coating process, but is not especially limited thereto. The film thus obtained is dried at 30-300°C and preferably 40-120°C to evaporate the organic solvents ahead of light exposure.

In step b), the film is selectively exposed to an electromagnetic wave through a photomask having a desired pattern. At this time, a crosslinking reaction takes place through photosensitive functional groups or photocurable compounds in the exposed area. This crosslinking reaction enables the formation of a network structure of semiconductor nanocrystals, resulting in a solubility difference between the exposed and unexposed areas. Based on the solubility difference, development of the film with a developing agent enables the formation of a negative pattern of semiconductor nanocrystals. The light exposure may be carried out by a contact or non-contact exposure process. In addition, the exposure dose is not especially limited, and can be

appropriately controlled according to the thickness of the film formed. It is preferred that the light exposure is carried out at an exposure dose of 50-850 mJ/cm<sup>2</sup>. When the exposure dose is insufficient, a crosslinking reaction is not likely to take place, or a photo bleaching occurs, which causes poor luminescence efficiency of the patterned nanocrystals. A light source usable for the light exposure preferably has an effective wavelength range of 200-500nm, preferably 300~400nm, and has an energy range of 100-800W.

In step c), the exposed film is developed with an appropriate developing agent to form a semiconductor nanocrystal pattern. Examples of developing agents usable in the present invention include organic solvents, such as toluene and chloroform, weakly acidic solutions and weakly basic solutions, and pure water.

Since the semiconductor nanocrystal pattern formed by the method of the present invention exhibits excellent luminescence characteristics, it can be utilized in a variety of fields, including semiconductor devices, e.g., displays, sensors and solar cells. Particularly, the pattern is useful in forming the luminescent layer of an organic-inorganic hybrid electroluminescent device. When the pattern is used to form a luminescent layer, it preferably has a thickness of 5-100nm. In the organic-inorganic hybrid electroluminescent device, organic layers are formed in an electron transport

layer or a hole transport layer except luminescent layer.

The organic electroluminescent device has a structure selected from anode/luminescent layer/cathode, anode/buffer layer/luminescent layer/cathode, anode/hole transport layer/luminescent layer/cathode, anode/buffer layer/hole transport layer/luminescent layer/cathode, anode/buffer layer/hole transport layer/luminescent layer/electron transport layer/cathode, and anode/buffer layer/hole transport layer/luminescent layer/hole blocking layer/cathode , but is not particularly limited to these structures.

As for buffer layer materials, compounds commonly used in the art for this purpose can be used. Preferred examples include, but are not limited to, copper phthalocyanine, polythiophene, polyaniline, polyacetylene, polypyrrole, polyphenylene vinylene and derivatives thereof. As materials for the hole transport layer, compounds commonly used in the art for this purpose can be used but the preferred is polytriphenylamine. As materials for the electron transport layer, compounds commonly used in the art for this purpose can be used but the preferred is polyoxadiazole. As materials for the hole blocking layer, compounds commonly used in the art for this purpose can be used. Preferred examples include, but are not limited to, LiF, BaF<sub>2</sub>, MgF<sub>2</sub> and the like.

The organic-inorganic hybrid electroluminescent device of the present invention does not require particular

manufacturing apparatuses and methods and can be manufactured using materials commonly known in the art, in accordance with conventional manufacturing methods.

5 Hereinafter, the present invention will be described in more detail with reference to the following examples and preparative examples. However, these examples are given for the purpose of illustration and are not to be construed as limiting the scope of the invention.

10 Preparative Example 1: Preparation of green emitting CdSeS nanocrystals surface-coordinated with a compound containing a double bond

15 16g of trioctylamine (hereinafter, referred to as 'TOA'), 0.5g of oleic acid and 0.4mmol of cadmium oxide were introduced simultaneously into a 125ml flask equipped with a reflux condenser. The temperature of the mixture was raised to 300°C with stirring. Separately, selenium (Se) powder was dissolved in trioctyl phosphine (hereinafter, referred to as  
20 'TOP') to obtain Se-TOP complex solution (Se concentration: about 0.25M), and sulfur (S) powder was dissolved in TOP to obtain S-TOP complex solution (S concentration: about 1.0M). 0.9ml of the S-TOP complex solution and 0.1ml of the Se-TOP complex solution were rapidly added to the reactant mixture,  
25 and then reacted for 4 minutes with stirring. Immediately

after the reaction was completed, the reaction mixture was rapidly cooled to room temperature. Ethanol as a non-solvent was added to the reaction mixture, and the resulting mixture was then centrifuged. After the obtained precipitate was separated from the mixture by decanting the supernatant, it was dispersed in toluene in the concentration of 1wt%. Peak emitting wavelength was about 520nm in the electroluminescence spectrum of the nanocrystals, and the nanocrystals emitted green light under 365nm UV lamp.

Preparative Example 2: Preparation of blue emitting CdSeS nanocrystals surface-coordinated with a compound containing a double bond

CdSeS nanocrystals were prepared in the same manner as in Preparative Example 1, except that the concentration of Se in the Se-TOP complex solution was set to 0.06M, and the concentration of S in the S-TOP complex solution was set to 2.0M. Peak emitting wavelength was about 480nm in the electroluminescence spectrum of the nanocrystals, and the nanocrystals emitted blue light under 365nm UV lamp.

Preparative Example 3: Preparation of CdS nanocrystals surface-coordinated with a compound containing a double bond

2.5ml of TOA was introduced into a 25ml flask equipped with a reflux condenser, and then the temperature was raised

to 180°C with stirring. A solution of 50mg of cadmium dithio diethyl carbamate in 0.9ml of TOP was rapidly added to the TOA, and then reacted for 10 minutes with stirring.

Immediately after the reaction was completed, the reaction mixture was rapidly cooled to room temperature. Ethanol as a non-solvent was added to the reaction mixture, and the resulting mixture was then centrifuged. After the obtained precipitate was separated from the mixture by decanting the supernatant, it was dispersed in toluene in the concentration of 1wt%. Then, oleic acid was added to the dispersion in the concentration of 5mM. The resulting mixture was refluxed at 70°C with stirring. For better surface-binding ability, the nanocrystals were separated from the solvent and dispersed again in toluene followed by adding oleic acid in the concentration of 5 mM and refluxing the mixture for 24hours at 70°C with stirring. The above procedure was repeated several times to prepare desired nanocrystals of which the surface was substituted with oleic acid. The final nanocrystals were dispersed in toluene. The peak emitting wavelength in the electroluminescent spectrum of the nanocrystals was 510nm, and the nanocrystals emitted bluish-green light under 365nm UV lamp.

Preparative Example 4: Preparation of CdSeS nanocrystals surface-coordinated with a compound containing acryl and vinyl

groups

To the dispersion of the nanocrystals prepared in Preparative Example 1, 3-mercapto-1-propanol was added in the concentration of 32mM. After the resulting mixture was  
5 refluxed at room temperature with stirring for 10 hours, the nanocrystals coordinated with 3-mercapto-1-propanol were separated through centrifuge and then dispersed in toluene in the concentration of 1wt%. 2g of the dispersion were introduced into a 250ml three-neck flask in an ice bath, and  
10 50g of tetrahydrofuran and 0.1g of triethylamine (TEA) were added thereto. The reactant mixture was stirred under nitrogen gas for 30 minutes. After 0.15g of methacryloyl chloride was added dropwise to the mixture using a dropping funnel, the reaction was continued for 4 hours. Then, adducts  
15 of salts were filtered off using a 0.1 $\mu$ m filter. Thereafter, the reaction mixture was washed with 100ml of distilled water in a separatory funnel to remove unreacted reactants and residual salts. The supernatant was separated from the dispersion in which semiconductor nanocrystals were dispersed,  
20 and remaining solvents were removed in a rotary evaporator under nitrogen gas to obtain nanocrystals. The resulting nanocrystals were again dispersed in toluene. The above procedure was repeated several times to obtain a toluene dispersion of final nanocrystals of which the surface was  
25 substituted with acryl and vinyl groups.

Preparative Example 5: Preparation of CdS nanocrystals  
surface-coordinated with a compound containing acryl group

2.5ml of TOA was introduced into a 25ml flask equipped  
5 with a reflux condenser, and then the temperature was raised  
to 180°C with stirring. A solution of 50mg of cadmium dithio  
diethyl carbamate in 0.9ml of TOP was rapidly added to the  
TOA, and then reacted for 10 minutes with stirring.

Immediately after the reaction was completed, the reaction  
10 mixture was rapidly cooled to room temperature. Ethanol as a  
non-solvent was added to the reaction mixture, and the  
resulting mixture was then centrifuged. After the obtained  
precipitate was separated from the mixture by decanting the  
supernatant, it was dispersed in toluene in the concentration  
15 of 1wt%.

3-Mercapto-1-propanol was added to the dispersion in the  
concentration of 32mM. After the resulting mixture was  
refluxed at room temperature for 10 hours with stirring, it  
was centrifuged to separate the nanocrystals surface-  
20 coordinated with the 3-mercapto-1-propanol. The obtained  
nanocrystals were again dispersed in toluene in the  
concentration of 1wt%. Thereafter, 50g of tetrahydrofuran and  
0.1g of triethylamine (TEA) were added to 2g of the  
dispersion. The mixture was stirred under nitrogen gas for 30  
25 minutes. After 0.15g of methacryloyl chloride was added



dropwise to the mixture using a dropping funnel, the reaction was continued for 4 hours. At this time, adducts of salts were filtered off using a 0.1 $\mu$ m filter. The reaction mixture was washed with 100ml of distilled water in a separatory funnel to remove unreacted reactants and residual salts. The supernatant was separated from the dispersion in which semiconductor nanocrystals were dispersed, and remaining solvents were removed in a rotary evaporator under nitrogen gas to prepare nanocrystals. The resulting nanocrystals were again dispersed in toluene. The above procedure was repeated several times to obtain a toluene dispersion of final nanocrystals of which the surface was substituted with acryl group.

Example 1: Formation of a green emitting CdSeS nanocrystal pattern

The dispersion (1wt%) of CdSeS nanocrystals prepared in Preparative Example 1 was spin coated onto a glass substrate cleaned with IPA at 2,000rpm for 30seconds to provide a semiconductor nanocrystal film. The film was dried at 50°C for 1 minute, and then at 100°C for 1 minute to completely evaporate solvents. Then, the film was exposed to 800W UV light having an effective wavelength of 200-300nm through a mask having a desired pattern for 300 seconds. The exposed film was developed with toluene to form a semiconductor

nanocrystal pattern. Fig. 2 is a photograph showing the emitting state of the pattern under 365nm UV lamp. From the photograph, it was confirmed that the nanocrystal pattern was consistent with that of the photomask used, and emitted green light. The peak emitting wavelength was about 520nm, showing the same result as that of the electroluminescent spectrum of the nanocrystals prepared in Preparative Example 1. In addition, the emitting peak had a full width half maximum (hereinafter, referred to as "FWHM") of approximately 40nm.

Example 2: Formation of nanocrystal pattern using a photosensitive composition

2.5ml of TOA was introduced into a 25ml flask equipped with a reflux condenser, and then the temperature was raised to 180°C with stirring. A solution of 50mg of cadmium dithio diethyl carbamate in 0.9ml of TOP was rapidly added to TOA, and then reacted for 10 minutes with stirring. Immediately after the reaction was completed, the reaction mixture was rapidly cooled to room temperature. Ethanol as a non-solvent was added to the reaction mixture, and the resulting mixture was then centrifuged. After the obtained precipitate was separated from the mixture by decanting the supernatant, it was dispersed in toluene in the concentration of 1wt%. 2g of the dispersion and 0.0005g of dipentaerythritol hexaacrylate (DPHA) were homogeneously mixed to prepare a composition.

Then, the composition was spin coated onto a glass substrate cleaned with IPA, at 2,000rpm for 30 seconds to provide a film. The film was exposed to 800W UV light having effective wavelength of 200-300nm through a mask having a desired pattern for 300 seconds. The exposed film was developed with toluene to form a semiconductor nanocrystal pattern. It was observed that the nanocrystal pattern emitted bluish-green light under 365nm UV lamp. It was confirmed from the observation that the nanocrystal pattern was consistent with that of the photomask used. The peak emitting wavelength was about 510nm in the electroluminescent spectrum of the pattern.

Example 3: Formation of green emitting CdSeS nanocrystal pattern using a photosensitive composition

0.2g of the toluene solution (1wt%) of CdSeS nanocrystals prepared in Preparative Example 1, and 0.0005g of dipentaerythritol hexaacrylate (DPHA) were homogeneously mixed to prepare a photosensitive composition. The composition was spin coated onto a glass substrate cleaned with IPA, at 2,000rpm for 30 seconds to provide a film. Then, the film was exposed to 800W UV light having an effective wavelength of 200-300nm through a mask having a desired pattern for 300 seconds. The exposed film was developed with toluene to form a semiconductor nanocrystal pattern. Fig. 3 is a photograph showing the emitting state of the nanocrystal pattern under

365nm UV lamp. From the photograph, it was confirmed that the nanocrystal pattern was consistent with that of the photomask used, and emitted green light. The peak emitting wavelength was about 520nm, showing the same result as that of the electroluminescent spectrum of the nanocrystals prepared in Preparative Example 1. In addition, the emitting peak had FWHM of approximately 40nm.

Example 4: Formation of blue emitting CdSeS nanocrystal pattern using a photosensitive composition

0.05g of the toluene solution (1wt%) of CdSeS nanocrystals prepared in Preparative Example 2, and 0.001g of DPHA were homogeneously mixed to prepare a composition. The composition was spin coated onto a glass substrate cleaned with IPA, at 2,000rpm for 30 seconds to provide a film. Then, the film was exposed to 800W UV light having an effective wavelength of 200-300nm through a mask having a desired pattern for 300 seconds. The exposed film was developed with toluene to form a semiconductor nanocrystal pattern. Fig. 4 is a photograph showing the emitting state of the nanocrystal pattern under 365nm UV lamp. From the photograph, it was confirmed that the nanocrystal pattern was consistent with that of the photomask used, and emitted blue light. The peak emitting wavelength was about 480nm, and had FWHM of approximately 40nm. Figs. 5a and 5b are an optical microscopic

image (x 1,000) and an AFM image of the semiconductor nanocrystal pattern. From the Figs. 5a and 5b, it was known that the CdSeS nanocrystals were uniformly dispersed in CdSeS nanocrystal pattern.

5

Example 5: Patterning of CdS nanocrystals surface-coordinated with a compound containing a carbon-carbon double bond

0.05g of the toluene solution (1wt%) of CdS nanocrystals surface-coordinated with oleic acid prepared in Preparative Example 3, was spin coated onto a glass substrate cleaned with IPA, at 2,000rpm for 30 seconds to provide a semiconductor nanocrystal film. The film was dried at 50°C for 1 minute, and then at 100°C for 1 minute to completely evaporate solvents. Then the film was exposed to 800W UV light having an effective wavelength of 200-300nm through a mask having a desired pattern for 300 seconds. The exposed film was developed with toluene to form semiconductor nanocrystal pattern. It was confirmed that the nanocrystal pattern was consistent with that of the photomask used, and emitted bluish-green light.

Example 6: Patterning of CdSeS nanocrystals surface-coordinated with a compound containing an acryl group

0.05g of the toluene solution (1wt%) of CdSeS

nanocrystals surface-coordinated with a compound containing an acryl group, as prepared in Preparative Example 4, was spin coated onto a glass substrate cleaned with IPA, at 2,000rpm for 30 seconds to provide semiconductor nanocrystal film. The film was dried at 50°C for 1 minute and then at 100°C for 1 minute to completely evaporate solvents. Then, the film was exposed to 800W UV light having an effective wavelength of 200-300nm through a mask having a desired pattern for 300 seconds. The exposed film was developed with toluene to form semiconductor nanocrystal pattern. It was confirmed that the nanocrystal pattern was consistent with that of the photomask used, and emitted green light.

Example 7: Patterning of CdS nanocrystals surface-coordinated with a compound containing acryl group

0.05g of the toluene solution (1wt%) of CdS nanocrystals surface-coordinated with a compound containing an acryl group, as prepared in Preparative Example 5, was spin coated onto a glass substrate cleaned with IPA, at 2,000rpm for 30 seconds to provide a semiconductor nanocrystal film. The film was dried at 50°C for 1 minute and then at 100°C for 1 minute to completely evaporate solvents. Then, the film was exposed to 800W UV light having effective wavelength of 200-300nm through a mask having a desired pattern for 300 seconds. The exposed film was developed with toluene to form a semiconductor

nanocrystal pattern. It was confirmed that the nanocrystal pattern was consistent with that of the photomask used, and emitted green light.

5           Example 8: Manufacture of electroluminescent device  
using nanocrystal pattern

10           In this Example, an organic-inorganic hybrid  
electroluminescent device was manufactured by employing a thin  
pattern of the nanocrystals prepared in Preparative Example 1  
as a luminescent material. PEDOT (poly-3,4-  
15 ethylenedioxythiophene) as a hole transport layer was spin-  
coated onto a patterned ITO substrate to a thickness of 50nm,  
and then baked. The toluene solution (1wt%) of CdSe  
nanocrystals prepared in Preparative Example 1 was spin-coated  
20 onto the hole transport layer and dried to form a luminescent  
layer having a thickness of 5nm. The luminescent layer was  
exposed to 800W UV light having an effective wavelength range  
of 200-300nm through a mask for 200 seconds and the exposed  
film was developed with toluene. Alq3 (tris(8-  
25 hydroxyquinoline) aluminum) was deposited onto the luminescent  
layer to form an electron transport layer having a thickness  
of about 40nm. LiF and aluminum were sequentially deposited  
onto the electron transport layer to thickness of 1nm and  
200nm, respectively, to manufacture an organic-inorganic  
hybrid electroluminescent device.

An electroluminescent spectrum of the electroluminescent device is shown in Fig. 6. The spectrum confirms that light was emitted from the nanocrystals by electrons applied to the device. In the electroluminescent spectrum of the device,  
5 peak emitting wavelength was 520nm, and the FWHM was approximately 40nm. In addition, the intensity of the spectrum was 10 Cd/m<sup>2</sup> and the efficiency of the device was about 0.1%.

10 Although the preferred embodiments of the present invention have been disclosed for illustrative purposes, those skilled in the art will appreciate that various modifications, additions and substitutions are possible, without departing from the scope and spirit of the invention as disclosed in the  
15 accompanying claims.